

**Title: Demonstration of thick phase-pure  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> on a c-plane sapphire substrate using MOCVD**

**Abstract:** We demonstrated a metal-organic chemical vapor deposition (MOCVD) of smooth, thick, and monoclinic phase-pure gallium oxide (Ga<sub>2</sub>O<sub>3</sub>) on c-plane sapphire using silicon-oxygen bonding (SiO<sub>x</sub>) as a phase stabilizer. The corundum ( $\alpha$ ), monoclinic ( $\beta$ ), and orthorhombic ( $\varepsilon$ ) phases of Ga<sub>2</sub>O<sub>3</sub> with a bandgap in the 4.4 – 5.1 eV range, are promising materials for power semiconductor devices and deep ultraviolet (UV) solar-blind photodetectors. The MOCVD systems are extensively used for homoepitaxial growth of  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> on (001), (100), (010), and (201)  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> substrates. These substrates are rare/expensive and have very low thermal conductivity; thus, are not suitable for high-power semiconductor devices. The c-plane sapphire is typically used as a substrate for high-power devices. The  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> grows in the (201) direction on sapphire. In this direction, the presence of high-density oxygen dangling bonds, frequent stacking faults, twinning, and other phases and planes impede the heteroepitaxy of thick  $\beta$ -Ga<sub>2</sub>O<sub>3</sub>. Previously phase stabilizations with SiO<sub>x</sub> have been reported for tetragonal and monoclinic hafnia. We were able to grow ~580nm thick  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> on sapphire by MOCVD at 750 °C through phase stabilization using silane. The samples grown with silane have a reduction in the surface roughness and resistivity from 10.7 nm to 4.4 nm and from 371.75  $\Omega\cdot\text{cm}$  to 135.64  $\Omega\cdot\text{cm}$ , respectively. These samples show a pure-monoclinic phase determined by x-ray diffraction (XRD); have tensile strain determined by Raman strain mapping. These results show that a thick, phase-pure  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> can be grown on c-plane sapphire which can be suitable for creating power devices with better thermal management.

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